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PATENT APPLICATION

1765
#14/c
3/24/03

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kazuyoshi TAMURA et al.

Group Art Unit: 1765

Application No.: 09/696,955

Examiner: M. A. Anderson

Filed: October 27, 2000

Docket No.: 107703

For: SILICON FOCUS RING AND METHOD FOR PRODUCING THE SAME

AMENDMENT UNDER 37 C.F.R. §1.111

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the December 19, 2002 Office Action, and further to the March 14, 2003 personal interview between Applicants' representative and Examiner Anderson, please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel claims 2, 4, 6 and 7 without prejudice to or disclaimer of the subject matter contained therein.

Please replace claims 1 and 5 as follows:

5b D1
C1

1. (Amended) A silicon focus ring comprising silicon single crystal used as a focus ring in a plasma apparatus, wherein, in order to increase an intrinsic heavy metal gettering effect of the focus ring, a concentration of interstitial oxygen contained in the silicon focus ring is not less than 5×10^{17} atoms/cm³ and not more than 1.5×10^{18} atoms/cm³, and a nitrogen concentration in the silicon focus ring is not less than 5×10^{13} number/cm³ and not more than 5×10^{15} number/cm³.